

L Number	Hits	Search Text	DB	Time stamp
1	285	(wafer or substrate) same (developer or developing) adj (liquid or solution) same (wash\$3 or clean\$3 or rins\$3) adj (liquid or solution or solvent)	USPAT; US-PGPUB; DERWENT	2003/08/26 11:52
2	1228	(uv or ultraviolet or electron adj beam) same (wash\$3 or clean\$3 or rins\$3) adj (liquid or solution or solvent)	USPAT; US-PGPUB; DERWENT	2003/08/26 11:53
3	29	((wafer or substrate) same (developer or developing) adj (liquid or solution) same (wash\$3 or clean\$3 or rins\$3) adj (liquid or solution or solvent)) and ((uv or ultraviolet or electron adj beam) same (wash\$3 or clean\$3 or rins\$3) adj (liquid or solution or solvent))	USPAT; US-PGPUB; DERWENT	2003/08/26 12:15
4	27	((wafer or substrate) same (developer or developing) adj (liquid or solution) same (wash\$3 or clean\$3 or rins\$3) adj (liquid or solution or solvent)) same ((uv or ultraviolet or electron adj beam) same (wash\$3 or clean\$3 or rins\$3) adj (liquid or solution or solvent))	USPAT; US-PGPUB; DERWENT	2003/08/26 12:15
5	0	((((wafer or substrate) same (developer or developing) adj (liquid or solution) same (wash\$3 or clean\$3 or rins\$3) adj (liquid or solution or solvent)) same ((uv or ultraviolet or electron adj beam) same (wash\$3 or clean\$3 or rins\$3) adj (liquid or solution or solvent))) not (((wafer or substrate) same (developer or developing) adj (liquid or solution) same (wash\$3 or clean\$3 or rins\$3) adj (liquid or solution or solvent)) and ((uv or ultraviolet or electron adj beam) same (wash\$3 or clean\$3 or rins\$3) adj (liquid or solution or solvent)))	USPAT; US-PGPUB; DERWENT	2003/08/26 12:15